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In this work, a p-n heterojunction film consisting of n-type WO<sub>3</sub> and p-type CuFe<sub>2</sub>O<sub>4</sub> was synthesized via two steps. The ntype WO<sub>3</sub> film was deposited on the FTO substrate by a doctor-blade method and then modified with p-type CuFe<sub>2</sub>O<sub>4</sub> nanoparticles by a deposition-annealing method. The composite film was characterized by X-ray powder diffraction, scanning electron microscopy, transmission electron microscopy, X-ray photoelectron spectroscopy and UV-vis diffuse reflectance spectroscopy, showing that the CuFe<sub>2</sub>O<sub>4</sub> nanoparticles were deposited on the surface of WO<sub>3</sub> film. Meanwhile, <u>photoelectrochemical</u> measurements were used to investigate the photoelectrochemical properties. A <u>photoeurrent</u> of 0.75 mA/cm<sup>2</sup> at 0.6 V (vs. Ag/AgCl) was achieved with CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub>, resulting in a 2.68 fold increase compared to pristine WO<sub>3</sub>. The presence of p-n heterojunction facilitates the separation of <u>photoinduced</u> electrons and holes, leading to more efficient charge transfer, resulting in a significant improvement in PEC performance.

# 1. Introduction

To solve the severe energy crisis and environmental pollution issues caused by the excessive consumption of traditional fossil fuels (coal, crude oil and natural gas) in the past decades, a lot of research has been reported. Among them, photoelectrochemical (PEC) water splitting, as an efficient, green and promising approach to generate renewable energy from sunlight, has triggered enormous research activities since Honda and Fujishima's report <sup>1</sup>. To date, various kinds of semiconductor materials have been synthesized and investigated <sup>2, 3</sup>. Because of its photosensitivity, chemical stability and environmental friendliness, tungsten trioxide (WO<sub>3</sub>) has been regarded as one of the ideal materials for solar-driven water splitting <sup>4</sup>.

Even though WO<sub>3</sub> has these promising characteristics, further improving the <u>photoelectrochemical</u> performance is necessary in order to satisfy practical application requirements. Besides loading WO<sub>3</sub> on the conductive substrates (FTO or ITO) is in favor of the reuse and recycle of photocatalyst, most of the researchers have

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Electronic Supplementary Information (ESI) available: [details of any supplementary information available should be included here]. See DOI: 10.1039/x0xx00000x focused on broadening the photoresponse region of semicondutor or improving the separation of the photo-generated electrons and holes <sup>5-7</sup>. The main methods for achieving the goal have included noble metal deposition <sup>8, 9</sup>, metal or non-metal element doping <sup>5, 6, 10, 11</sup>, surface modification <sup>12</sup>, or coupled with other semiconductors <sup>13-18</sup>. Among them, coupled with other semiconductors, which can promote the separation of the photoinduced electron-hole pairs via the different position of valence and conduction band from each other, is an effective method to improve the efficiency of water splitting.

 $MFe_2O_4$  (M = Cu, Zn, Co et.al), which is a high thermal stable material with effective catalytic activity, has been used extensively in photocatalysis and solar water-splitting <sup>19-21</sup>. Since most of the ferrates are p-type semiconductors, some of them can couple with ntype semiconductors to form p-n heterojunction composite particles (CuFe<sub>2</sub>O<sub>4</sub>/CdS, CuFe<sub>2</sub>O<sub>4</sub>/SnO<sub>2</sub>, CuFe<sub>2</sub>O<sub>4</sub>/TiO<sub>2</sub> and CaFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub>) <sup>14, 22-24</sup>. For example, Miyauchi et al. prepared CaFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> composite powders by mechanically mixing n-type WO3 with p-type CaFe<sub>2</sub>O<sub>4</sub> particles, and the composite photocatalyst showed better performance than WO<sub>3</sub> on the photocatalytic decomposition of acetaldehyde 14. The enhanced photocatalysis activity can be ascribed to the separation of the photo-generated electron-hole pairs by their potential difference at the p-n heterojunction. Even though the powdered composite photocatalyst is a great candidate in photocatalysis, its application is limited due to the low recyclability. To cover the shortage, loading p-type ferrate on the surface of ntype semiconductor film is expected to be an efficient route. Even though several works on the photocatalysis or photoelectrochemical property of n-type semi-conductor with p-type semiconductor (ferrate <sup>25, 26</sup>, Cu<sub>2</sub>O <sup>27-30</sup>, NiO <sup>31</sup>, Si <sup>32</sup>, CdTe <sup>33</sup> and BiOI <sup>34</sup> et.al) film have been reported, the n-type WO<sub>3</sub> film loaded with ferrate is lack of attention. To the best of our knowledge, this is the first report to

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study the photoelectrochemical performance of  $WO_3$  film loaded with  $CuFe_2O_4$  nanoparticles.

In this paper, we fabricated the  $CuFe_2O_4/WO_3$  p-n heterojunction film by doctor-blade method and depositionannealing method. Meanwhile, the photoelectrochemical properties had been systematically characterized by several methods, including linear sweep <u>voltammetry</u>, electrochemical impedance spectroscopy (EIS), Mott–Schottky and incident photon to current conversion efficiency (IPCE).

# 2. Experimental

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# 2.1 Preparation of $CuFe_2O_4\!/WO_3$ heterojunction film

All chemicals were analytical grade and were used without further purification. In a typical synthesis, the WO<sub>3</sub> spherical nanopowders were prepared by a solution method <sup>35</sup>. Then, 0.175 g obtained WO<sub>3</sub> <u>nanopowders</u> were added to an agate jar with <u>terpineol</u> (0.8 mL) as a solvent. PEG20000 (0.05 g) and <u>ethylcellulose</u> (0.025 g) were added to the agate jar as additive. Besides, 0.2 mL acetylacetone and 0.2 mL triton were also added to the agate jar. The WO<sub>3</sub> paste was acquired after Ball Milling for 8 h. The WO<sub>3</sub> films were fabricated by the doctor blade method on the FTO glass substrates that had been cleaned up. Finally, the as-prepared WO<sub>3</sub> films were calcined at 450 °C for 0.5 h.

A deposition-annealing method was used to synthesize the  $CuFe_2O_4$  nanoparticles on the as-prepared WO<sub>3</sub> film (1.5 cm × 1 cm). In detail, 0.060 g of Cu(CH<sub>3</sub>COO)<sub>2</sub>·H<sub>2</sub>O was dissolved into 10 mL of de-ionized (DI) water to form a transparent solution firstly (solution A). Then, 0.196 g of K<sub>3</sub>Fe(CN)<sub>6</sub> was dissolved into another 30 mL of DI water to form a transparent solution (solution B). After the two solutions were stirred for 10 min in the ice bath, respectively, the solution A was added into the solution B drop by drop under vigorously stirred in the ice bath. After further stirred in the ice bath for another 1 h, the asprepared WO<sub>3</sub> film was put into the solution. The mixture was transferred into a refrigerator, keeping at 0-4 °C in a refrigerator for 2 h. Then the film was taken out and washed by dipping in the DI water for 30 seconds. After drying at 60 °C, the CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> film was calcined at 500 °C for 1h. For comparison, the pristine WO3 film and the mixed solution were also calcined to prepare pure WO3 and bare CuFe2O4, respectively.

# 2.2 Characterization

The phase formations of the as prepared films were determined by an X-ray diffractometer (D/Max2250). The morphology of the materials was studied with a field emission scanning electron microscope (FESEM, NanoSEM 230) equipped with an Energy Dispersive X-ray (EDX) analyzer and a transmission electron microscope (TEM, TECNAI G2 F20). The surface elemental analysis was carried out by an X-ray photoelectron spectroscopy (XPS, ESCALAB 250Xi). UV-vis spectra were determined using a UV-vis spectrophotometer (UV-vis, PGeneral TU-1901) in diffuse reflectance mode.

# 2.3 Photoelectrochemical measurements

The PEC performance of films was characterized by a typical three-electrode electrochemical cell with an electrochemical analyzer (Zennium, Zahner, Germany), using an Ag/AgCl (saturated KCl) reference electrode and a platinum counter electrode. A 0.2 M Na<sub>2</sub>SO<sub>4</sub> aqueous solution was used as electrolyte all of for photoelectrochemical tests. Photocurrent-potential plots were characterized by linear sweep voltammogram at 20 mV/s under AM 1.5G illumination, and the scanned range was from 0 to 1.0 V (vs. Ag/AgCl). The electrochemical impedance spectra (EIS) were recorded at 0.3 V (vs. Ag/AgCl) with a 10 mV AC voltage perturbation, and the frequency were varied from 10,000 to 0.1 Hz. Additionally, incident photon to electron conversion efficiency (IPCE) of the film was obtained as a function of wavelength from 310 to 700 nm, and the absolute intensity of the monochromic incident light was measured by a silicon photodiode.

# 3. Results and discussion

The XRD patterns of WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> films are shown in Fig.1. It can be easily seen that the XRD pattern of each sample matchs well with the standard monoclinic phase WO<sub>3</sub> (JCPDS no. 83-0950). Moreover, there are also some peaks corresponding to tetragonal SnO<sub>2</sub> (JCPDS no.46-1088), meaning that the samples were loaded on the FTO substrate. The XRD pattern of the bare CuFe<sub>2</sub>O<sub>4</sub> was also measured as shown in Fig. S1. The peaks at 2 $\theta$  values of 18.32, 30.18, 35.60 and 37.10 <sup> $\beta$ </sup> can be indexed to (111) (220) (311) and (222) crystal planes of CuFe<sub>2</sub>O<sub>4</sub> or other materials are not observed in CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> (Fig.1), which indicates that the concentration of CuFe<sub>2</sub>O<sub>4</sub> is too low to be detected by XRD.

The SEM images of the WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> films are presented in Fig. 2. In Fig.2a and 2b, the top-view of <u>SEM</u> images exhibit that both samples are <u>nanoporous</u> network composed of spherical particles, which are agglomerate and interconnected each other. As can be seen in the cross sectional images (Fig. 2c and 2d), the thickness of both WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> films are about 3.2  $\mu$ m however, the layer of CuFe<sub>2</sub>O<sub>4</sub> can not be found. It means that CuFe<sub>2</sub>O<sub>4</sub> may



Fig.1 XRD patterns of WO\_3 and CuFe\_2O\_4/WO\_3 films

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Fig. 2 SEM images of the surface morphology of (a) WO<sub>3</sub> and (b)  $CuFe_2O_4/WO_3$  films; cross-sectional micrographs of (c)  $WO_3$  and (d)  $CuFe_2O_4/WO_3$  films

compactly deposit on the surface of WO<sub>3</sub> film. Furthermore, the energy dispersive X-ray (EDX) analyses were recorded as shown in the Fig. S2, and Cu and Fe can be detected in the sample of  $CuFe_2O_4/WO_3$  (Fig. S2b).

To get more detailed information on the crystalline structure of the composite, the TEM images of  $CuFe_2O_4/WO_3$  at different magnifications are displayed in Fig. 3. The low resolution image (Fig. 3a) shows the particles are spheres that are highly

agglomerated, and the size of the sphere is approximately 40 nm. It can also be seen that a smaller particle with irregular size adhere to the sphere. Fig. 3b displays the lattice fringes of the smaller particle and sphere. The interplanar distances observed in the smaller particle and the sphere are 0.254 and 0.365 nm, which correspond to the 311- and 200-planes of tetragonal CuFe<sub>2</sub>O<sub>4</sub> and monoclinic WO<sub>3</sub>, respectively. It is proved that CuFe<sub>2</sub>O<sub>4</sub> nanoparticles are attaching to the WO<sub>3</sub> to form CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> composite.

The presence of CuFe<sub>2</sub>O<sub>4</sub> on the surface of WO<sub>3</sub> film was further confirmed by the XPS spectra (Fig.4). In Fig.4a, the survey spectrum of WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> indicates peaks of elements W and O. The carbon peak is attributed to adventitious hydrocarbon from the XPS instrument itself, which is not indicated in the Figure. Fig. 3b shows the XPS spectrum of the tungsten core level (W 4f). The two peaks at 35.47 and 37.62 eV in the spectrum can be assigned to W  $4f_{7/2}$  and W  $4f_{5/2}$ , respectively, which are consistent with the reported values <sup>36</sup>. Fig.4c and 4d show the high-resolution XPS spectra for Fe 2p and Cu 2p, respectively. From the Fe 2p spectrum, it was found that the peaks at 711.2 and 724.7 eV are from Fe 2p3/2 and Fe 2p1/2, and two accompanying satellite peaks visible at binding energies of around 718.4 eV is indicative of the presence of Fe<sup>3+</sup> cations <sup>37</sup>. Two distinct and intense peaks were appeared for the Cu 2p spectrum, which are Cu 2p3/2 = 932.6eV and Cu 2p1/2 = 952.4 eV ( $\Delta BE = 19.8$  eV) <sup>38</sup>. A satellite peak at about 942.0 eV can also be seen, which provides evidence for the presence of Cu<sup>2+ 37</sup>. The ICP analysis was employed to determine the concentration of various metals (Cu, Fe and W), and [Cu]:[Fe]:[W] value of 1.51:3.12:100 was estimated, so the ratio of p semiconductor to n semiconductor is about 1.51:100 in our system.



Fig. 3 (a) Transmission electron micrographs and (b) High resolution TEM (HRTEM) image of  $CuFe_2O_4/WO_3$ 

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### • Fig.4 XPS of CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> (a) full spectrum; (b) W 4f; (c) Fe 2p and (d) Cu 2p.

The UV-visible spectra of pure WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> films are presented in Fig.5. The bare WO<sub>3</sub> film absorbs light with wavelengths smaller than 455 nm, corresponding to 2.72 eV of band gap energy <sup>39</sup>. The <u>absorbance</u> edge of CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> is 463 nm, corresponding to 2.68 eV of band gap energy. The <u>slightly</u> shift of <u>absorbance</u> edge is probably due to the higher absorption coefficient of CuFe<sub>2</sub>O<sub>4</sub> for visible light

(Fig.S3). To investigate the flat band potential ( $V_{fb}$ ) of samples, Mott-Schottky plots were employed with a frequency of 500 Hz as shown in Fig. 6. The value of  $V_{fb}$  is approximately equal to the value of <u>x-intercept</u>, which are 0.08 and 0.19 V (vs. Ag/AgCl) for WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub>, respectively. It can be found that a positive shift of flat band potential, and a shift of the Fermi level to positive potential. It is because that CuFe<sub>2</sub>O<sub>4</sub>







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is a p-type semiconductor with a negative slope, whose flat band potential is about 0.5 V (vs. Ag/AgCl) (Fig.S4) <sup>31</sup>. Moreover, the potential of Fermi levels of WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub> is in equilibrium after forming the p-n heterojunction <sup>24</sup>. So the CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> has a positive flat band potential compared with pure WO<sub>3</sub> film.

To further study the effect of the valence band maximum (VBM) of the WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub>, the valence band X-ray photoelectron spectroscopy (VB XPS) was employed to determine the electronic structure. Fig. 7 indicates that the VBM of CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> moves to higher potential compared with that of WO<sub>3</sub>. That is to say, the VBM of the WO<sub>3</sub> changes after coupling with CuFe<sub>2</sub>O<sub>4</sub>, in agreement with the changing of flat band potential.

To investigate the photoresponsivity of the films, the photocurrent-potential was measured using a linear sweep voltammetry method as shown in Fig.8. The current values of two samples are about zero under dark condition. In the range of 0.3-1.0 V (vs. Ag/AgCl), a significant improvement of photocurrent under irradiation indicates the enhanced PEC activity after loading of CuFe2O4. A photocurrent of 0.75 mA/cm<sup>2</sup> (0.6 V vs. Ag/AgCl) was achieved with CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub>, which is 1.68 times higher than that of bare  $WO_3$  (0.28 mA/cm<sup>2</sup>), The conversion efficiency is about 0.48 % (Fig.S5), and it is higher than the results reported in the similar system <sup>35, 40</sup>. For a semiconductor thin film photoanode, the magnitude of photocurrent is determined by the competition of photo-generated carriers migration and recombination <sup>41</sup>. At the same time, most of the photogenerated electron/hole pairs recombine generating heat and/or light after excitationg <sup>42</sup>. In fact, p-n junction can greatly enhance the charge separation owing to the internal electric field 43. Hence, the p-n heterojunction formed by n-type WO3 and p-type CuFe2O4 has a beneficial effect on the separation of the photo-generated carriers and decreasing the recombination of electrons and holes. In addition, the onset potential of CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> (Fig.S6) shows a positive shift compared with pure WO<sub>3</sub>, which is consistent with the results of flat band potentials in Fig.6a. To observe the effect of composition (ratio of p/n) on the





- Fig.8 (a) Linear sweep voltammograms of WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub>, (b) transient photocurrent of WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub>

photoelectrochemical performance, various composite films were fabricated by changing the concentration of Cu(CH<sub>3</sub>COO)<sub>2</sub>·H<sub>2</sub>O and K<sub>3</sub>Fe(CN)<sub>6</sub> (the details in the supporting information), and the photocurrent curves are shown in Fig.S7. It can be concluded that the ratio of  $p/n \approx 1.51$ :100 might be the optimized composition in our system. Transient photocurrent were also measured at 0.4 V (vs. Ag/AgCl) with chopped light, as shown in Fig.6b. The photocurrent of both samples are about zero when the light is chopped, and the photocurrent show decay mode under irradiation, meaning that the recombination process occurs. The transient time constant  $(\tau_{\text{tran}})$  were calculated from the equation:  $\exp(-t/\tau_{\text{tran}}) = (I_t - I_f)/(I_t - I_f)$  $I_{f}$ ) <sup>44, 45</sup>. It is 3.5s for WO<sub>3</sub> and 4.5s for CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub>, respectively, indicating the p-n heterojunction accelerates the separation of photoinduced electrons and holes. The stability of WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> were also investigated, as shown in Fig.S8. After irradiation of 1140 s, the photocurrents of WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> decrease with 64.1% (from 0.100 to 0.036 mA/cm<sup>2</sup>) and 56.2% (from 0.442 to 0.194 mA/cm<sup>2</sup>), respectively. It means that the CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> film shows a little better stability compared to the bare WO<sub>3</sub> film.

EIS measurement was employed to study the electron transfer resistance across the electrode-electrolyte interfaces under visible irradiation. Fig.9a shows the Nyquist plots which can be used to characterize the charge transfer resistance and

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the separation efficiency of the photo-generated electrons and holes <sup>45</sup>. The impedance spectra, consisting of a semicircle, can be fitted with an appropriate equivalent circuit. As shown in Fig.9b, the equivalent circuit includes a series resistance  $(R_s)$ , a charge transfer resistance  $(R_{ct})$  and a constant phase element (CPE). The semicircle of CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> is smaller than that of WO<sub>3</sub>, and the fitting results of  $R_s$  are 2479 and 364 ohm for WO3 and CuFe2O4/WO3, respectively. It means that the p-n heterojunction decrease the charge transfer resistance at the interface of electrode and electrolyte, leading to more efficient charge separation. Correspondingly, the characteristic frequency peaks for WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> in Bode phase plots are shown in Fig.9c. The peak of CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> shifts to low frequency from 53.5 Hz to 10.0 Hz compared with WO<sub>3</sub>. Therefore, the lifetime of photoelectrons  $(\tau)$  for the films can be estimated by the equation:  $\tau = 1/2\pi f_{max}$ <sup>45</sup>, where  $f_{max}$  is the peak frequency, and the  $\tau$  are 3.0 and 15.9 ms for WO<sub>3</sub> and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub>, respectively. The presence of p-n heterojunction facilitates the separation of photoinduced electrons and holes, leading to prolongation of photoelectrons lifetime, resulting in a significant improvement in PEC performance.



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In order to further explore the quantitative correlation of light



absorption on the films, IPCE measurements were performed at

the bias of 1.0 V (Fig. 10). The light response region of  $WO_3$ and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> are both at 310-475 nm. The CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> film shows a higher IPCE value compared with WO<sub>3</sub> film in the whole photoresponse region. Moreover, the maximum IPCE value of CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> is 47.27% at 350 nm, which is 1.21 times higher than that of WO<sub>3</sub>. As the number of electrons in the external circuit produced by an incident photon at a given wavelength divided by the number of incident photons, IPCE is determined by three microscopic processes: light harvesting (LH), separation of opposing charges (CS), and a collection of the charges (CC) at the electrodes. Considering the similar light absorbance of two samples as shown in Fig. 5, the different value of IPCE at the whole light response region indicates that the separation of opposing charges is the main factor. So the improvement of photoelectrochemical performance is ascribed to the presence of p-n heterojunction.

Based on the above results, a simple mechanism of the conduction and valence band positions for  $CuFe_2O_4/WO_3$  is shown in Fig.11. The space charge region caused by p-n heterojunction has a beneficial effect of improving the charges separation <sup>22</sup>. In this way, photo-generated holes transfer to  $CuFe_2O_4$ , and more photo-generated electrons can transfer to conductive substrates without recombination. Therefore, it can be concluded that the p-n heterojunction promotes electron/hole separation, leading to an enhanced photoelectrochemical performance.

### Conclusion

In summary, the CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> p-n heterojunction film was synthesized and deposited on the FTO substrate by a doctorblade method and a deposition-annealing method. The results of TEM, SEM and XPS show that CuFe<sub>2</sub>O<sub>4</sub> nanoparticles were deposited on the surface of WO<sub>3</sub> film. Mott–Schottky and electrochemical impedance spectroscopy analysis confirmed the formation of p–n heterojunction, and CuFe<sub>2</sub>O<sub>4</sub>/WO<sub>3</sub> heterojunction film shows an enhanced photoelectorchemical properties compared to WO<sub>3</sub> film. The presence of p-n



heterojunction facilitates the separation of <u>photoinduced</u> electrons and holes, leading to more efficient charge transfer, resulting in a significant improvement in PEC performance.

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 $CuFe_2O_4$  was loaded on the surface of  $WO_3$  film to form p-n heterojunction photoanode with a better performance than  $WO_3$ .